

Measurement and Scalable Model for Parasitic PNP of HV PMOS

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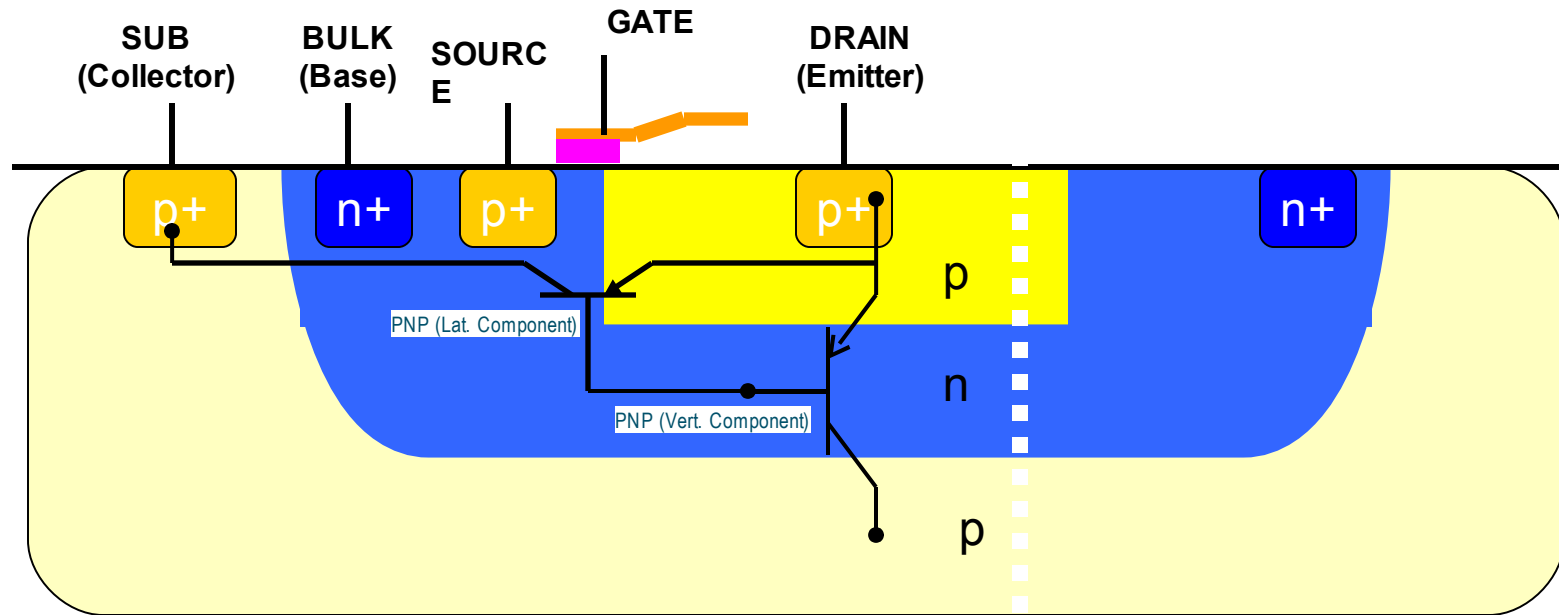
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Bipolar Arbeitskreis, 18-19 October 2007, Munich, Germany

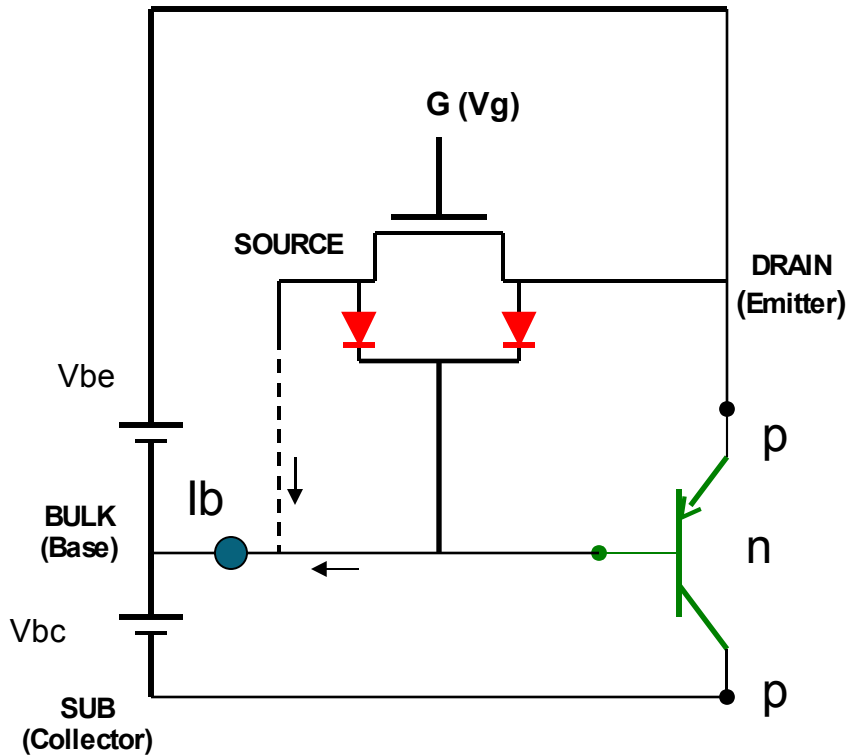
Outline

- ❖ Measurement configuration for parasitic PNP
 - Cross-section of HV PMOS device
 - Understanding of parasitic bipolar
 - Measurement results
- ❖ Analysis for high current gain
 - Current gain for different devices
 - High current gain
- ❖ Investigation on scalable model
 - Details collector current (I_c) and base current (I_b) scaling over width and length
 - Propose scaling equation
- ❖ Modeling of reverse operation
 - Reverse current gain < 1
 - Sub-circuit model for reverse operation
- ❖ Summary

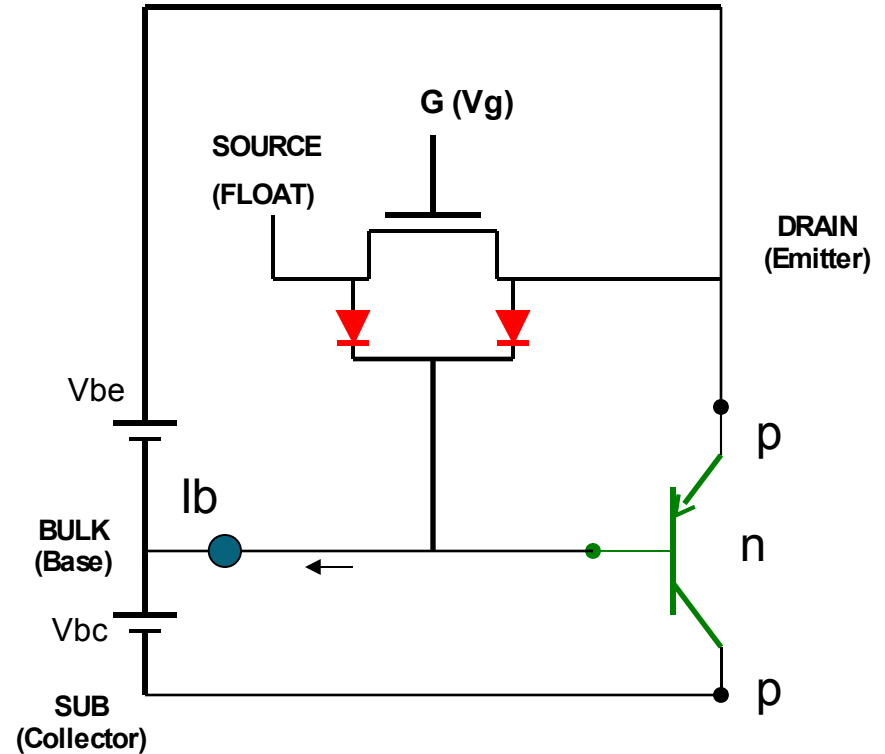
Understanding of Parasitic PNP



Measurement Conditions

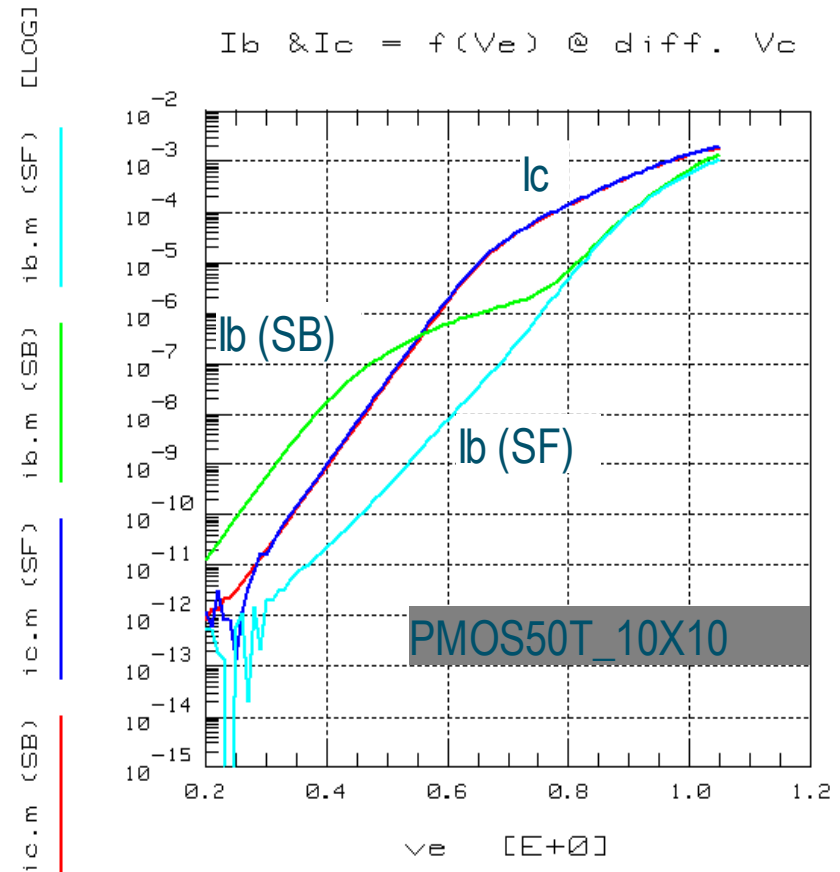
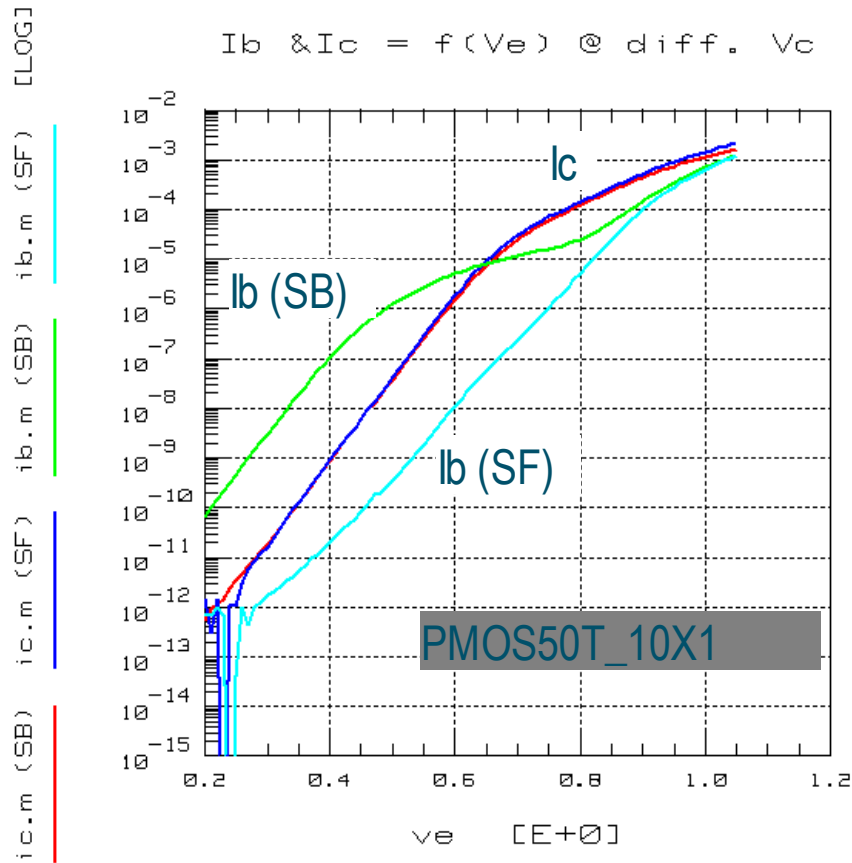


Source is connected with Bulk (SB)



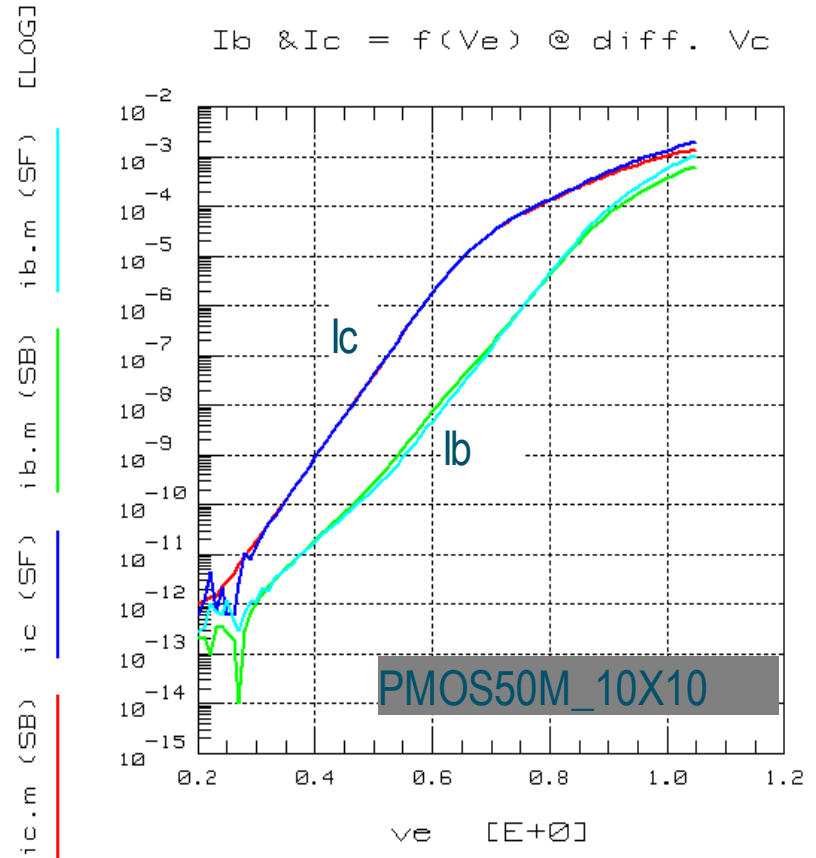
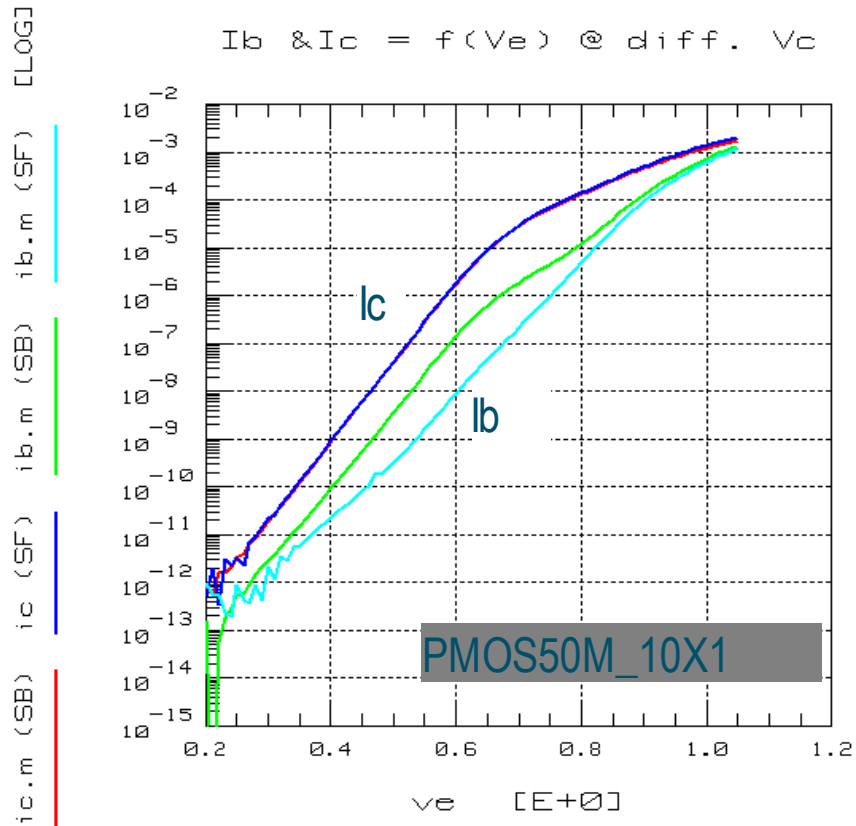
Source is floating (SF)

Measurement of PMOS50T (TOX = 7.5 nm)

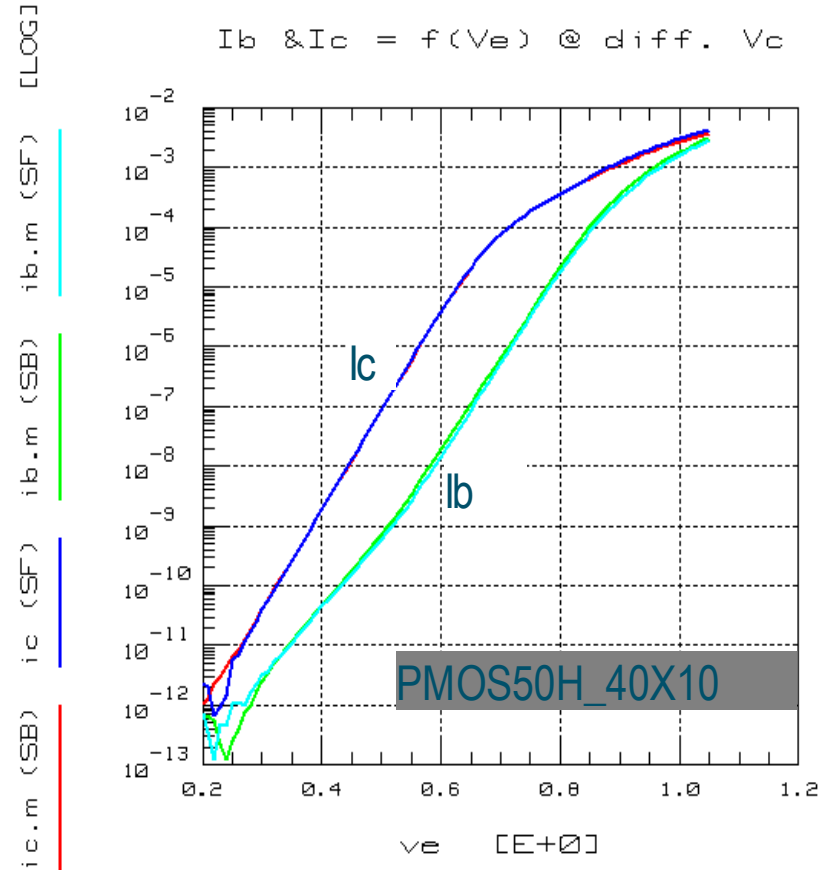
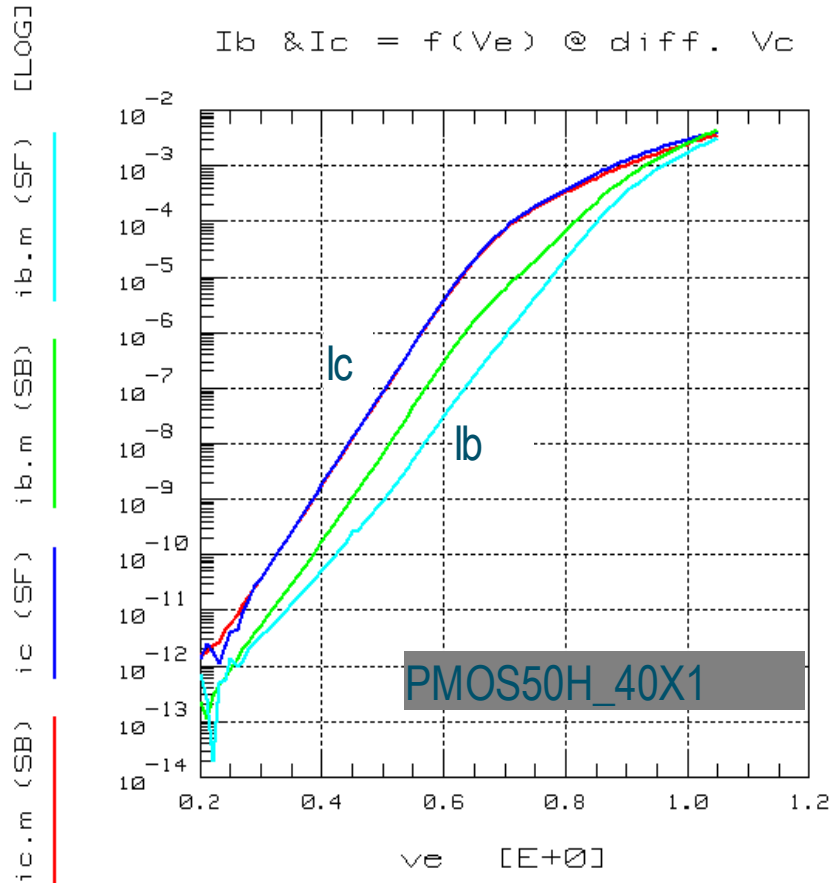


- Collector current has nearly same value for the both conditions
- Base current shows very high value for the SB condition due to leakage current from drain to source

Measurement of PMOS50M (TOX=15nm)



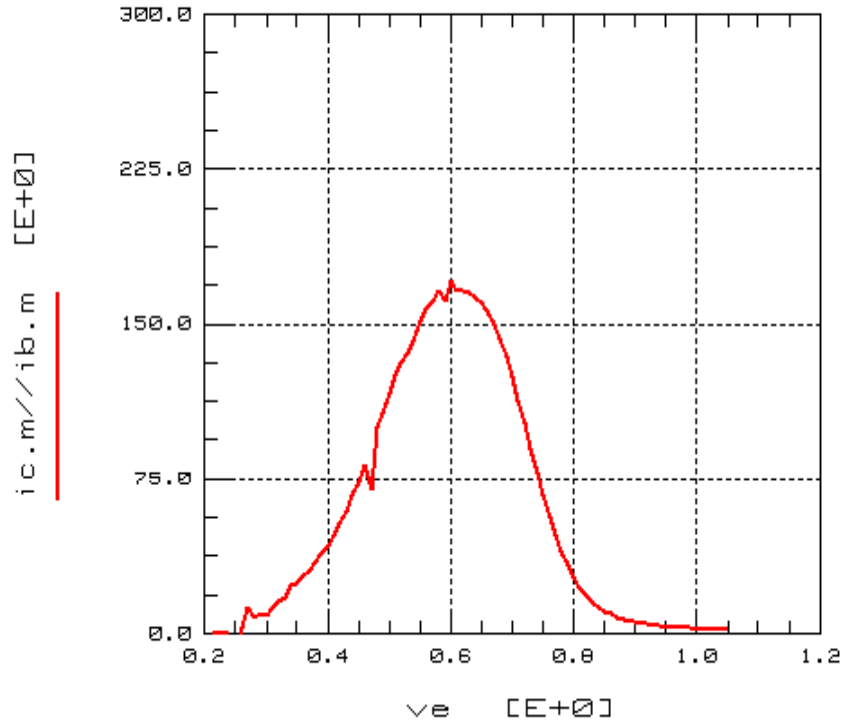
Measurement of PMOS50H (TOX=48 nm)



Analysis for high current gain

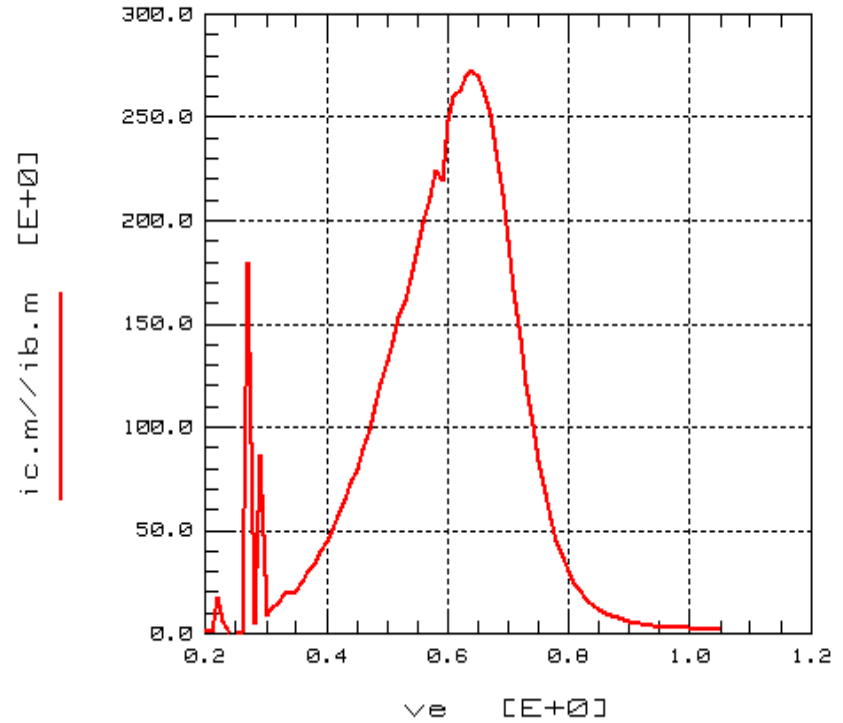
Current Gain: PMOS50T

$I_c/I_b = f(V_e) @ \text{diff. } V_c$



PMOS50T_10X1

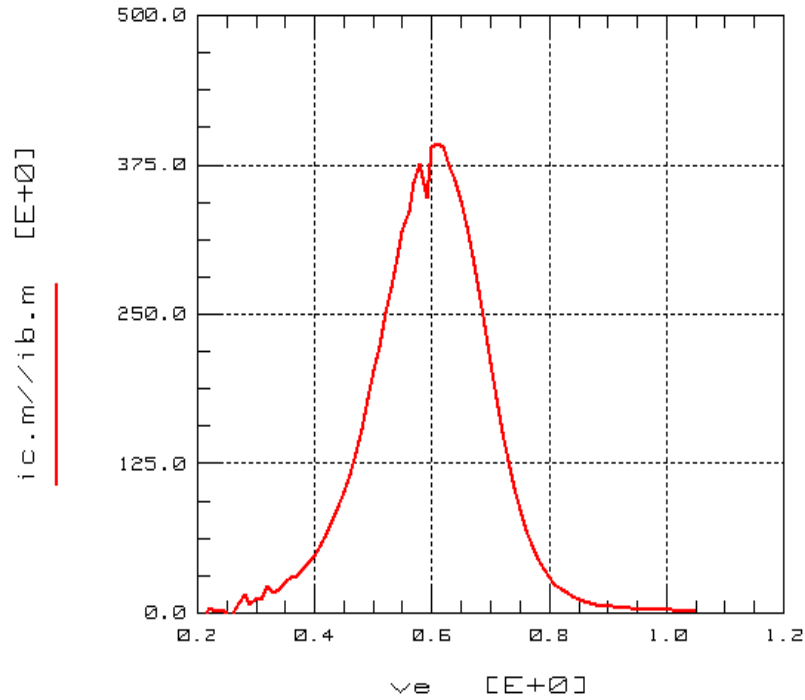
$I_c/I_b = f(V_e) @ \text{diff. } V_c$



PMOS50T_10X10

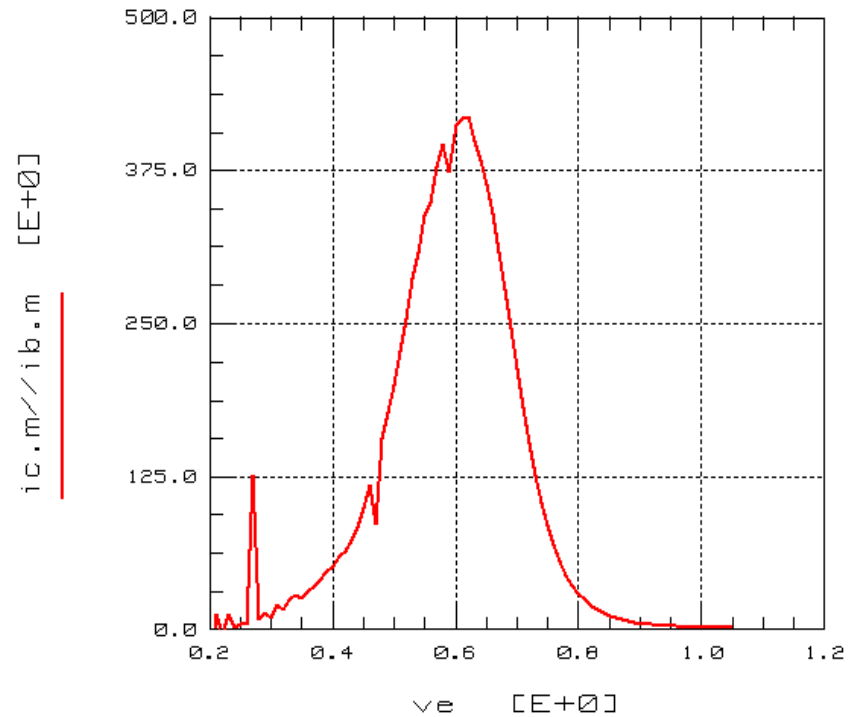
Current Gain: PMOS50M and PMOS50H

$I_c/I_b = f(V_e) @ \text{diff. } V_c$



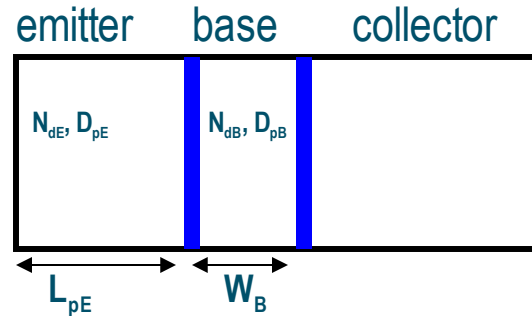
PMOS50M_10X10

$I_c/I_b = f(V_e) @ \text{diff. } V_c$



PMOS50H_10X10

Bipolar Gain

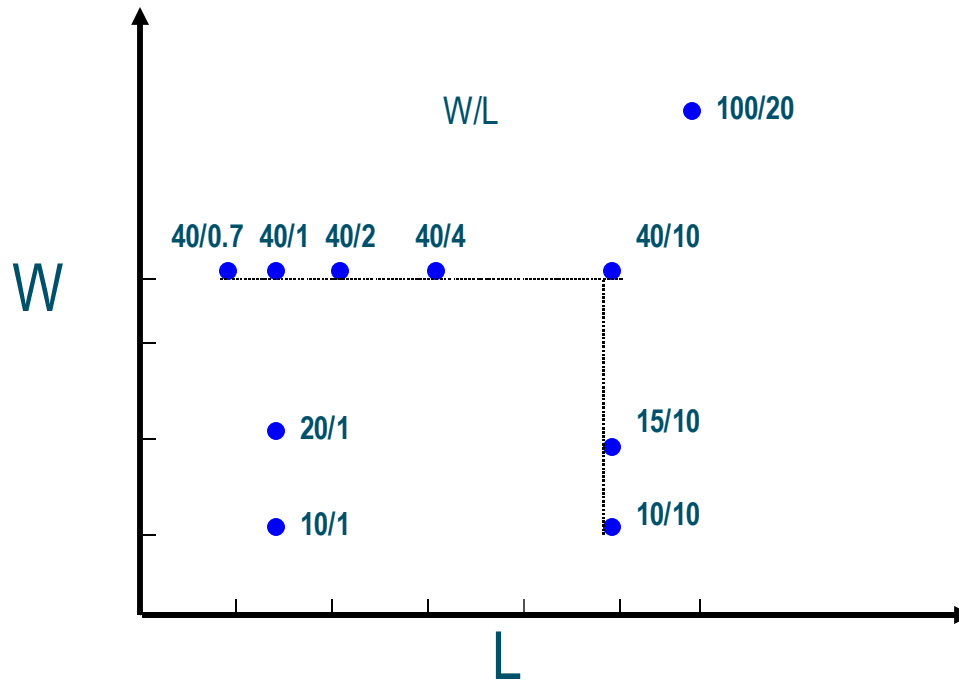


$$\beta_{\max} = \frac{N_{dE} * D_{nB} * L_{pE}}{N_{aB} * D_{pE} * W_B}$$

- Y-direction cross-section shows very thin base thickness
- Due to thin base, PNP shows very high current gain ($\beta_{\max} \sim 400$)

Investigation on scalable model

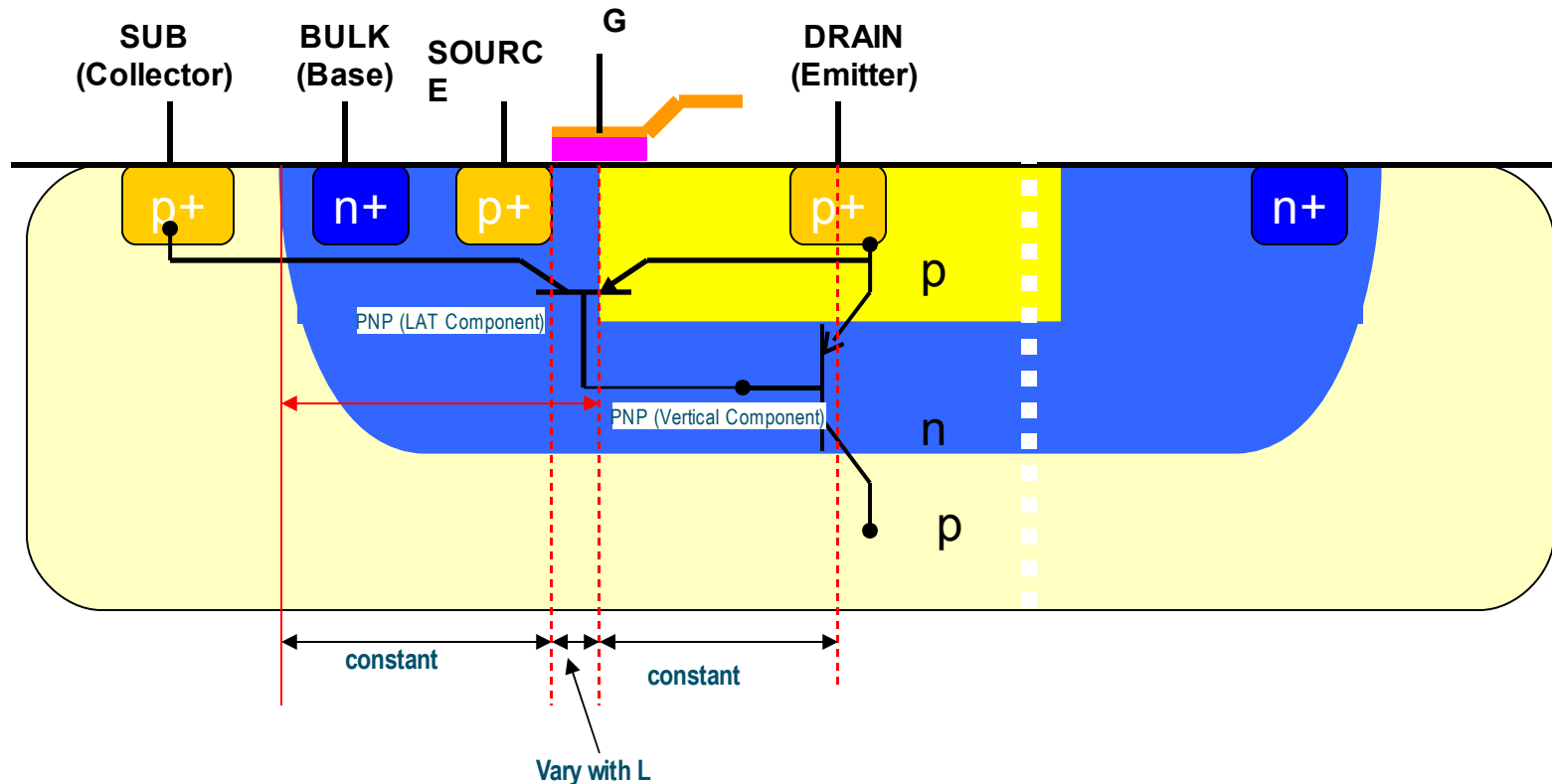
Geometry of 50V PMOSM



- Different geometries are available for the measurement

Scaling of Parasitic PNP

- PNP (both Vertical component and Lateral component) are scaled with W

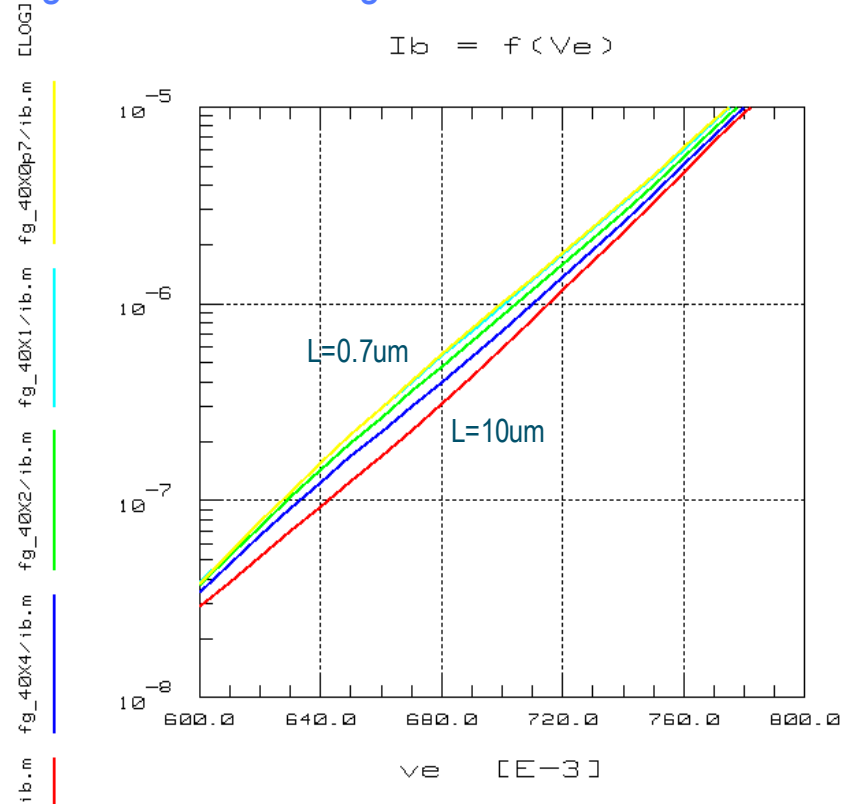
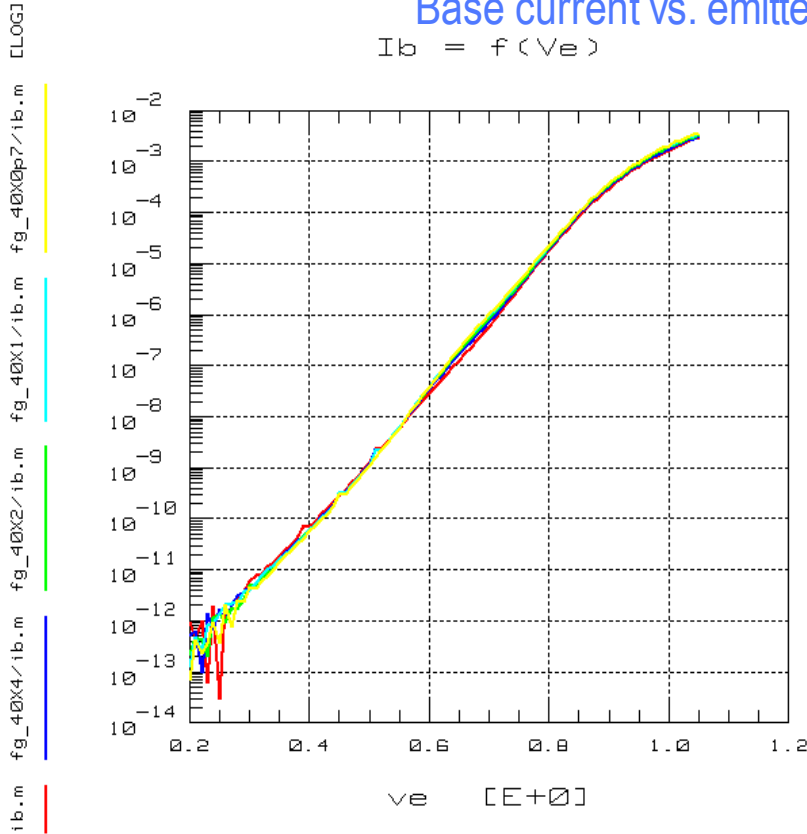


- PNP (Vertical component) does not vary with L
- PNP (Lateral component) base width vary with L

Length Scaling of PMOS50T (Ib)

Base current vs. emitter voltage for different lengths

$$I_b = f(V_e)$$

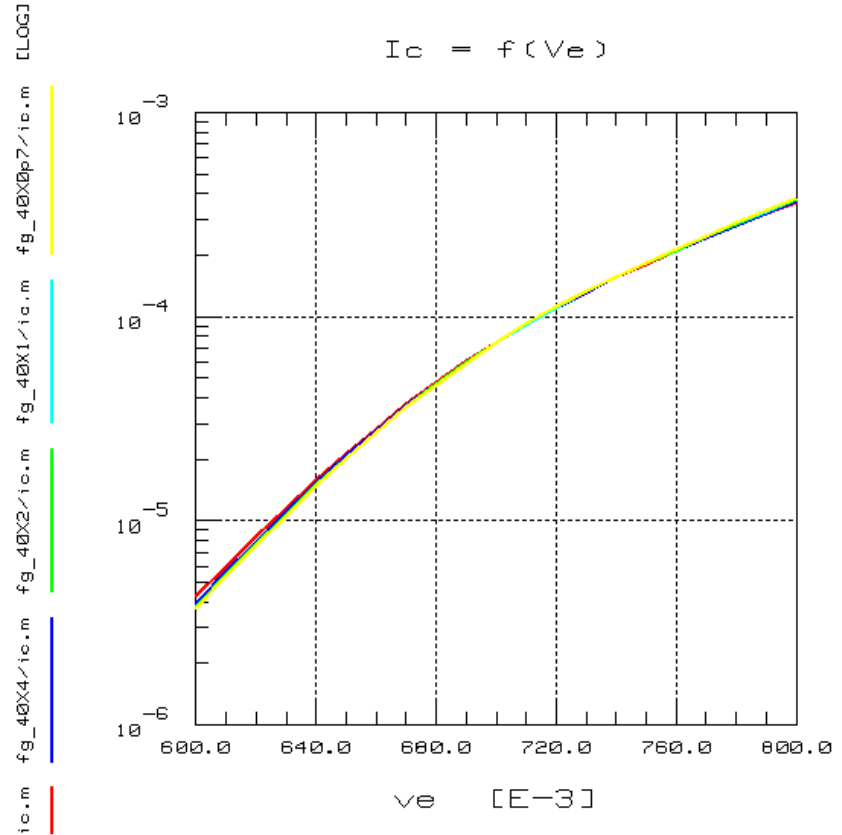
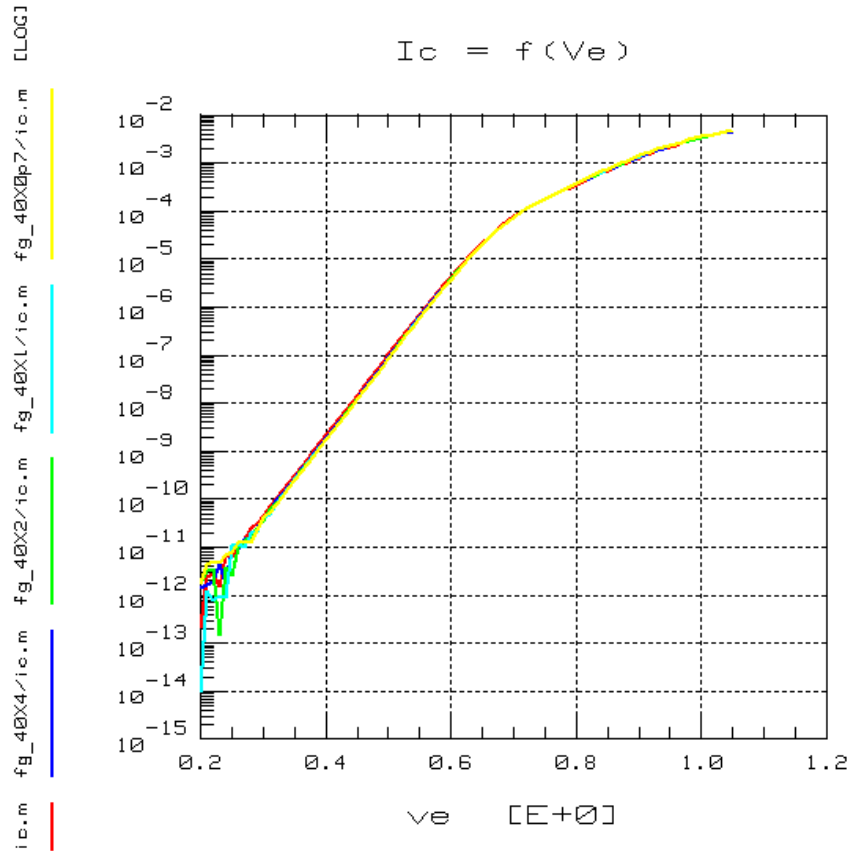


L = 10, 4, 2, 1, 0.7 um; W = 40 um

- As the L decreases base current increases, due to surface leakage current from drain to bulk

Length Scaling of PMOS50T (Ic)

Collector current vs. emitter voltage for different lengths

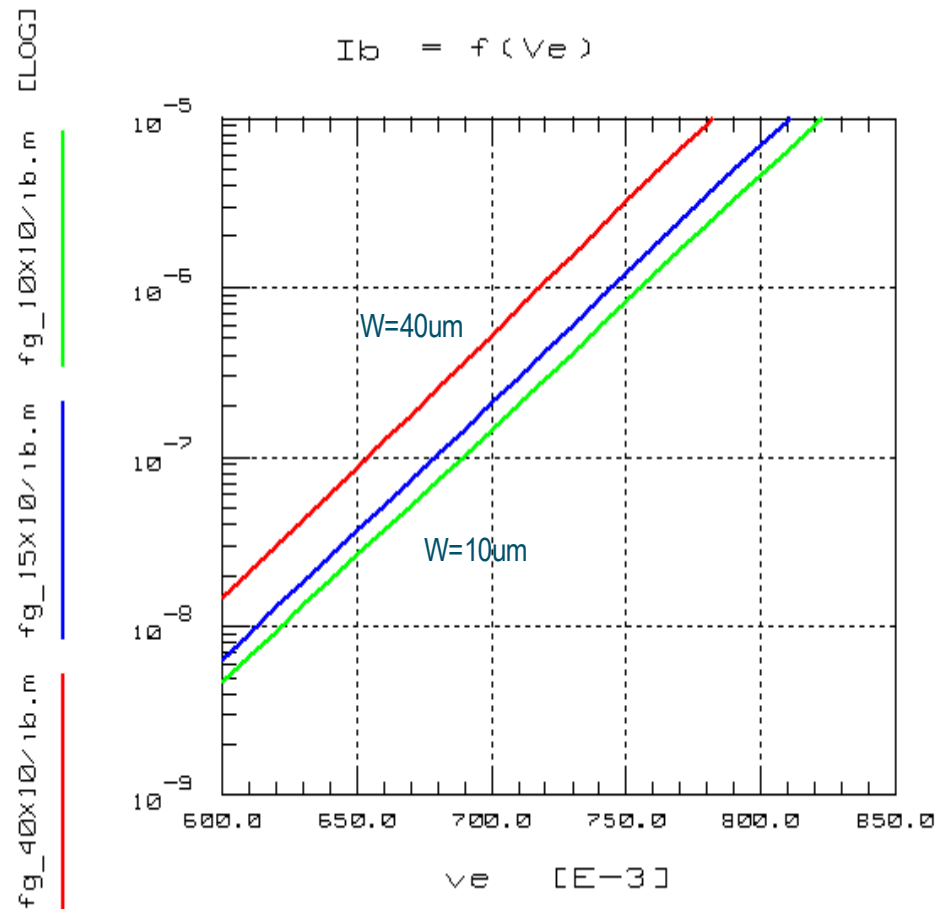
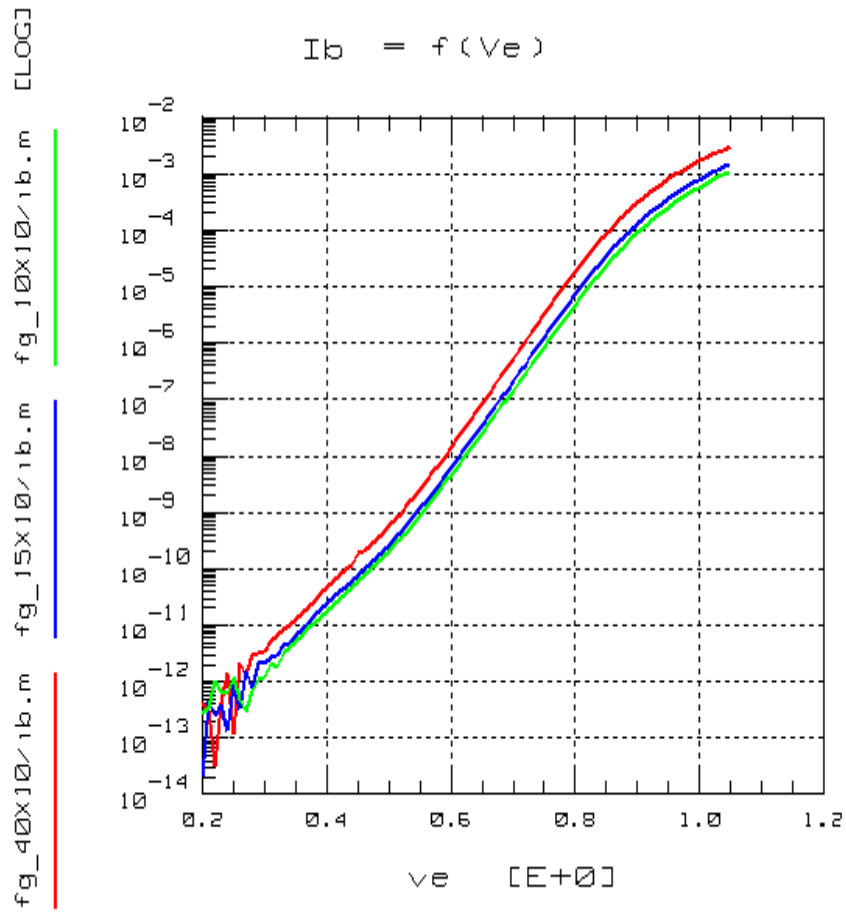


L = 10, 4, 2, 1, 0.7 μm ; W = 40 μm

- No significant change on the collector current over L

Width Scaling of PMOS50T (Ib)

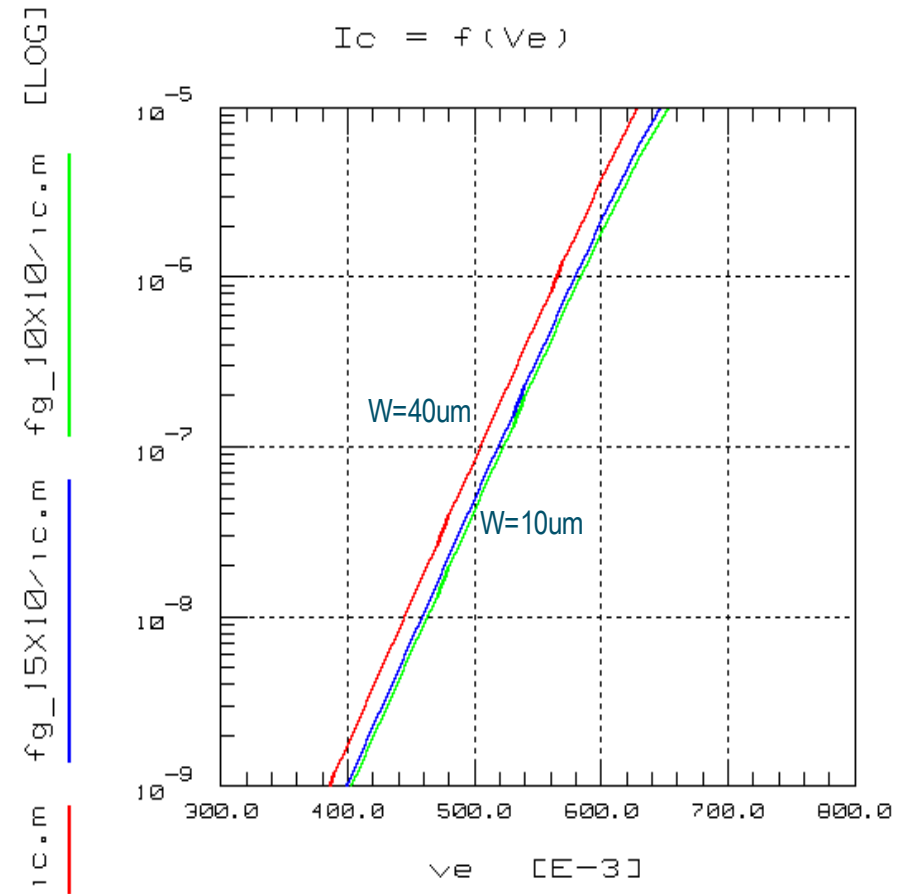
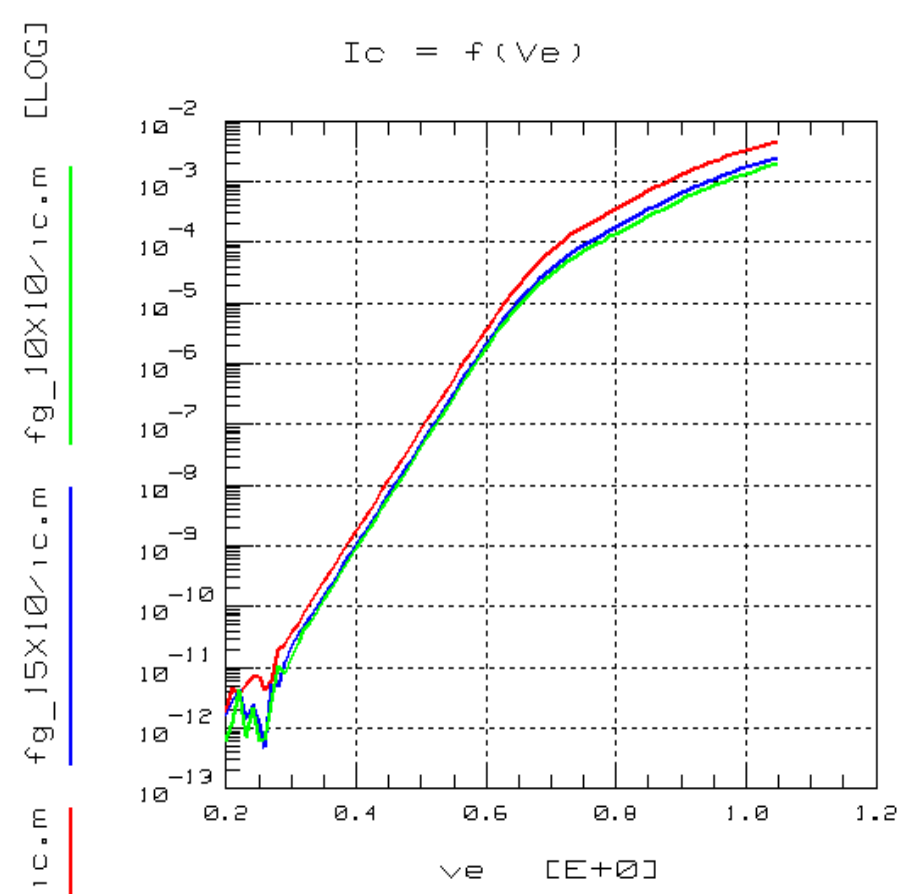
Base current vs. emitter voltage for different lengths



$L = 10\mu\text{m}; W = 40, 15, 10\ \mu\text{m}$

Width Scaling of PMOS50T (Ic)

Collector current vs. emitter voltage for different lengths



$L = 10\mu m$; $W = 40, 15, 10\mu m$

Scaling Equation for Model Parameters

- Standard SPICE Gummel-Poon model is used for the parasitic PNP

- Parameters scaling apply with W and L separately:

$$\mathit{parSCALE} = \mathit{parWSCALE} + \mathit{parLSCALE}$$

- Width scaling ($\mathit{parWSCALE}$) equation is used after fitting of each parameter with equation

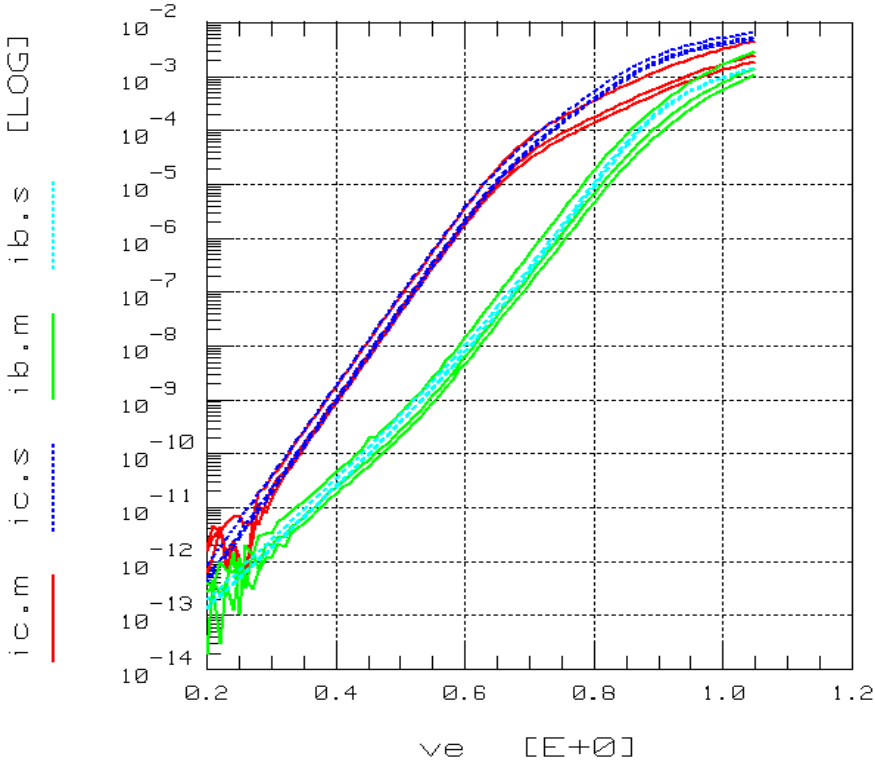
$$\mathit{parWSCALE} = \exp\left[\mathit{parw0} + \frac{\mathit{parw}}{W + \mathit{wpar0}}\right]$$

- Length scaling ($\mathit{parLSCALE}$) equation is used after fitting of each parameter with equation

$$\mathit{parLSCALE} = \mathit{parl0} * L$$

Scalable Model Results: Gummel Plot

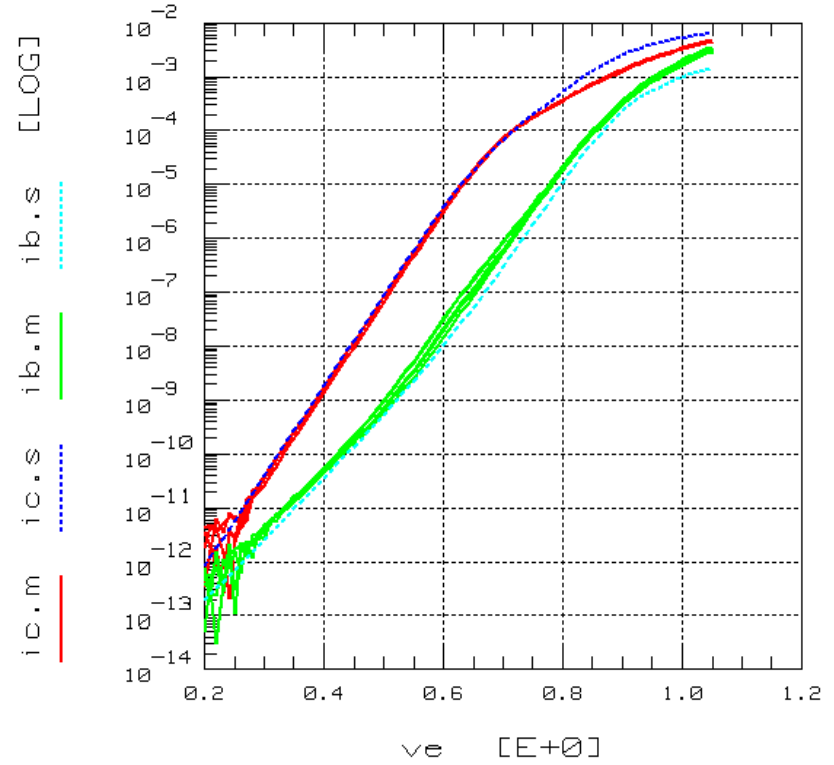
$I_b \ \& \ I_c = f(V_e) \ @ \ \text{diff. } V_c$



Width Scaling

$L = 10 \mu\text{m}; W = 40, 15, 10 \mu\text{m}$

$I_b \ \& \ I_c = f(V_e) \ @ \ \text{diff. } V_c$



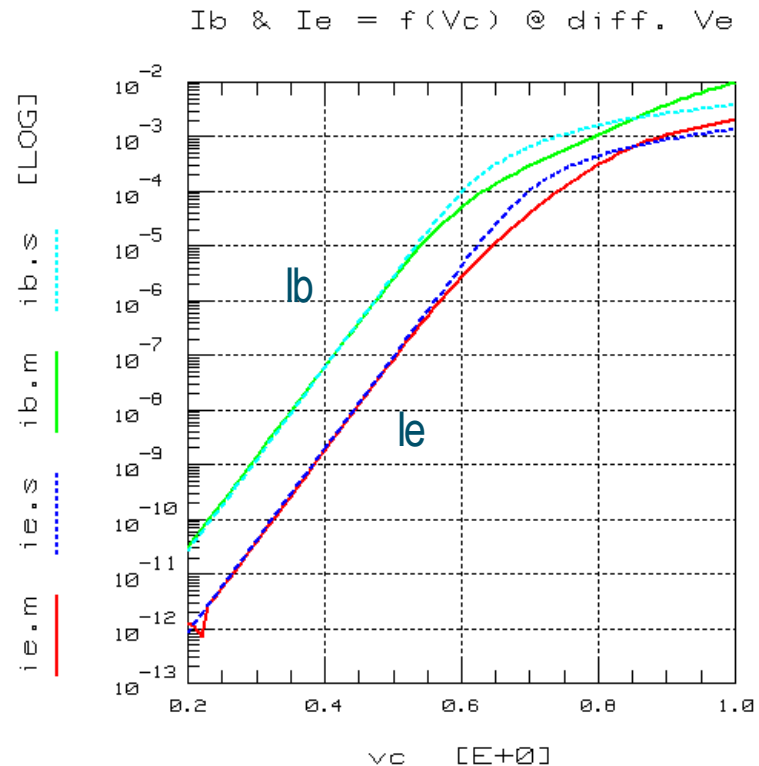
Length Scaling

$L = 10, 4, 2, 1, 0.7 \mu\text{m}; W = 40 \mu\text{m}$

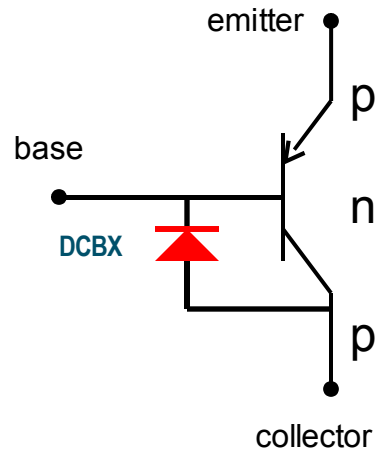
Modeling of Reverse Operation

Reverse Gummel Model

- Reverse current gain shows < 1
- After adjusting reverse current gain parameter (BR), it is possible to model reverse Gummel (RG), but impossible to model reverse output (RO)
- For simultaneously fitting both the RG and RO, need to an extra diode between collector and base



Sub-Circuits for modeling surface current



- Due to large area of substrate ring, large current flowing through the surface
- So need extra diode (DCBX) to model the surface current

Summary

- **Source floating conditions shows more accurate way to measure the parasitic PNP**
- **Due to thin base width, PNP shows very high current gain**
- **Scalable model is now sufficient for all geometries (W and L)**
- **Reverse mode operation can be modeled with extra diode**